

## **POSITIONING STAGE WITH STATIONARY AND MOVABLE MAGNET TRACKS**

### ABSTRACT OF THE DISCLOSURE

5           A stage positioning system including a stationary frame, a slide movable  
relative to the frame in a first direction, and a support platform connected to the slide  
and movable therewith in the first direction. The support platform is movably  
attached to the slide for movement in a second direction generally orthogonal to the  
first direction. The system will further include a first linear motor containing a first  
10   magnet assembly and a first coil device that engages the first magnet assembly to  
move the slide in the first direction. A second linear will contain a second magnet  
assembly and a second coil device that engages the second magnet assembly to move  
the support platform in the second direction. The stage positioning system is  
particularly suited for positioning an article in electron beam or EUV light  
15   lithography systems.